



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO. 050169/0105

In re Patent Application of Batch No.: K83
Wallace T.Y. TANG : Allowed: October 26, 1998
Serial No. 08/401,229 Group Art Unit: 2874
Filed: March 9, 1995 Examiner: J. Lee
For: IN-SITU REAL-TIME MONITORING TECHNIQUE AND
APPARATUS FOR ENDPOINT DETECTION OF THIN FILMS
DURING CHEMICAL/MECHANICAL POLISHING
PLANARIZATION

INFORMATION DISCLOSURE
STATEMENT UNDER 37 C.F.R. § 1.56

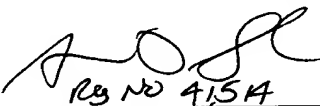
Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the duty of disclosure under 37
C.F.R. §§ 1.56 and 1.98, Applicant wishes to bring to the
attention of the U.S. Patent and Trademark Office the
references listed on the enclosed Form PTO-1449. Copies
of the listed references are enclosed.

Respectfully submitted,

March 17, 1999
Date


Stephen B. Maebius
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Should additional fees be necessary in connection with the filing of this paper, or if a petition for extension of time is required for timely acceptance of same, the Commissioner is hereby authorized to charge Deposit Account No. 19-0741 for any such fees; and applicant(s) hereby petition for any needed extension of time.

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FORM NO 1449 (modified)

ATTY DOCKET NO. 050169/0105

SERIAL NO. 08/401,229

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICE

APPLICANT: Wallace T.Y. TANG

LIST OF REFERENCES CITED BY APPLICANT(S)
(Use several sheets if necessary)

FILING DATE: March 9, 1995

GROUP: 2874

Date Submitted to PTO: March 17, 1999

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

		A. Novembre	BACUS - 9th Annual Symposium, "Automated Process Control of Poly(Butene-1-Sulfone)
		et.al.	PBS Resist Development, (September 1989) pp. 139-144
		A. Novembre	SPIE, Vol. 1087, Integrated Circuit Metrology, Inspection, and Process Control-III (1989)
		et.al.	"An In Situ Interferometric Analysis of Resist Development on Photomask Substrates, pp. 460-468
		A. Novembre	SPIE, Vol. 1809, 12th Annual BACUS Symposium (1992), "Initial manufacturing performance of an actively
		et.al.	controlled PBS resist development process (pp. 76-84

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.